



19nm 112.8mm² 64Gb Multi-level Flash Memory with 400Mb/s/pin 1.8V Toggle Mode Interface

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Outline



- Introduction to 19nm 64 Gbit MLC NAND (400 Mb/s/pin interface)
- Chip Architecture for Small Die Size
- MLC Programs Techniques
- New Features(Read-Latency Reduction)
- Summary of Key Features
- Conclusion

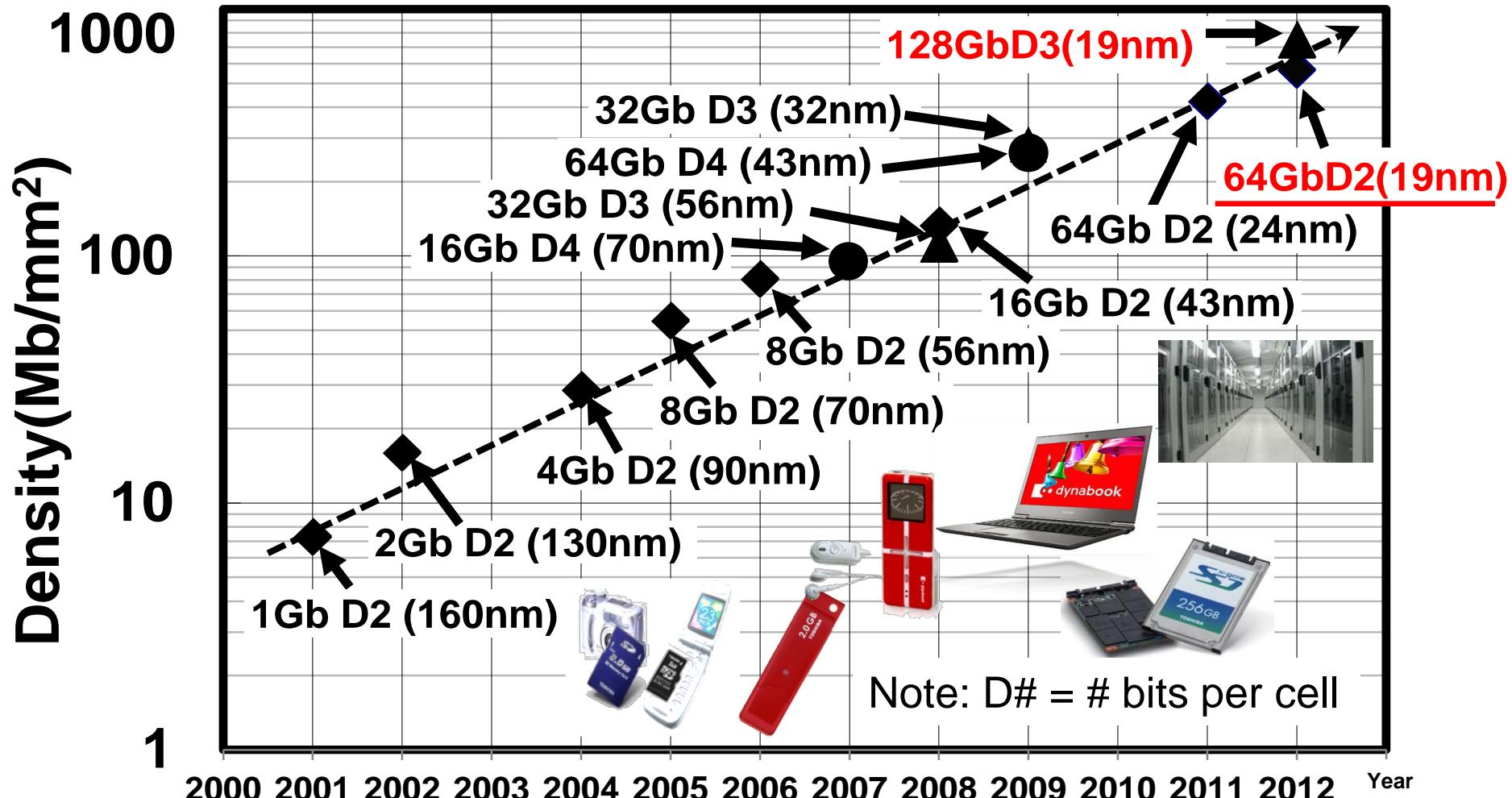


Outline



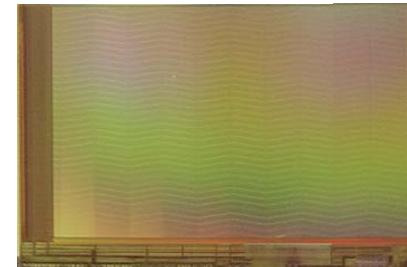
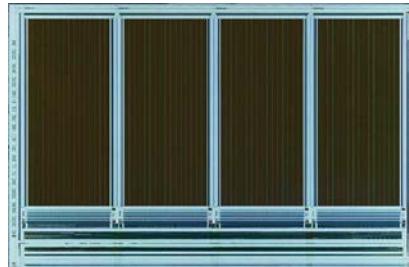
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NAND Flash Density Trend



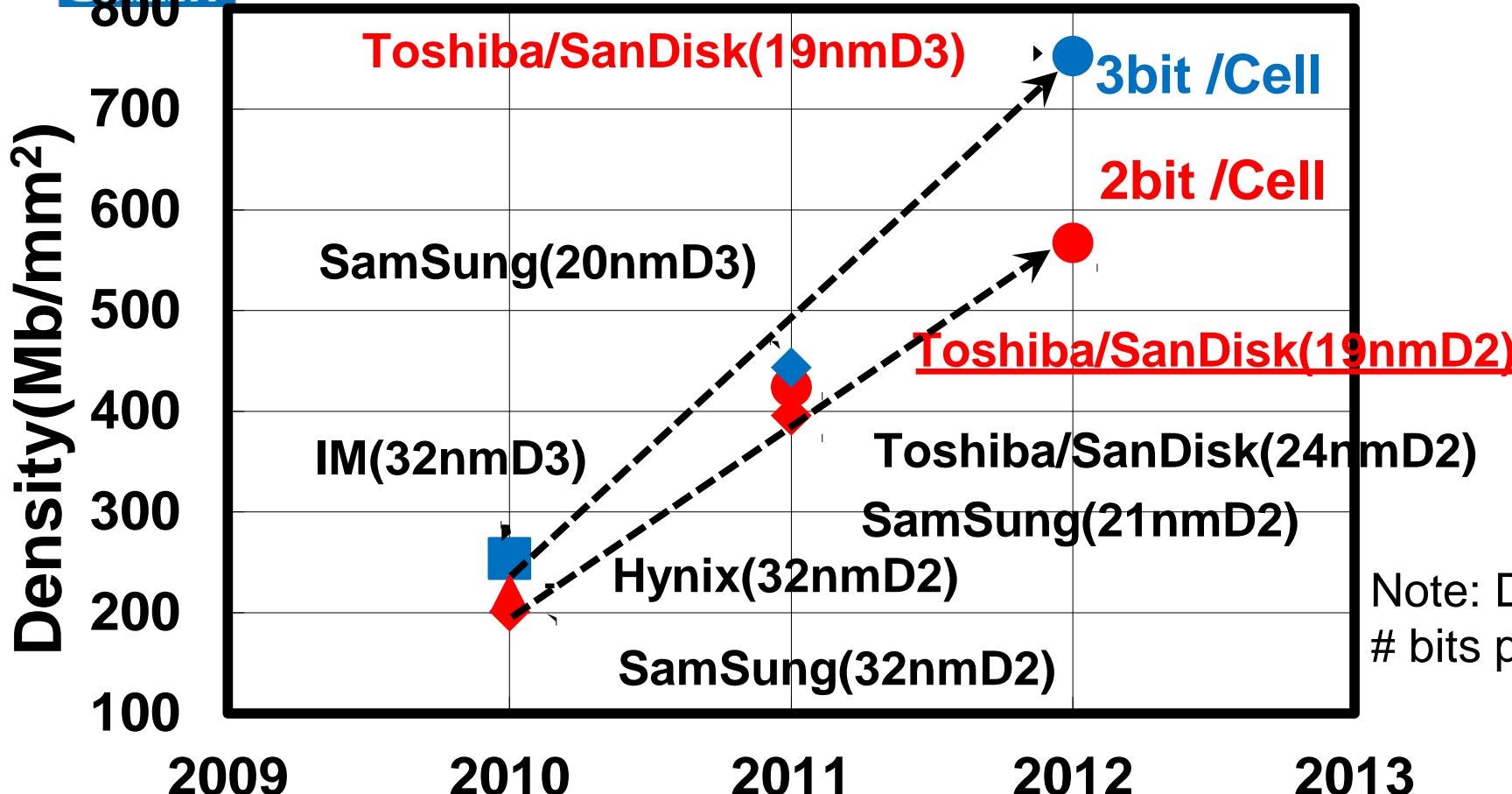
Since first 160nm 1Gb MLC was commercially introduced in 2001, Memory Density has expanded by over **100 times**

Comparisons of first 1Gb MLC and latest 64Gb MLC



Technology	160nm	one-ninth	19nm
Density	1Gb	64 times	64Gb
Die Size	137mm ²		112.8mm ²
Mb/mm ²	7.5	80 times	581
Architecture	Conventional Even / Odd		<u>All-Bit-Line(ABL)</u>
SA configuration	Both Sided		Single Sided
Program unit	2kB (= 512B x4Plane)	8 times	16kB (=16kB x1Plane)
tProg	1.1ms		1.1ms
Prog. Perform.	1.9MB/s	8 times	15MB/s
Burst Cycle Time	20Mb/s/pin(50ns)	20 times	400Mb/s/pin(2.5ns)
Year	2001	10 years	2011

Comparisons of 3bit /cell and 2bit /cell



Note: D# =
bits per cell

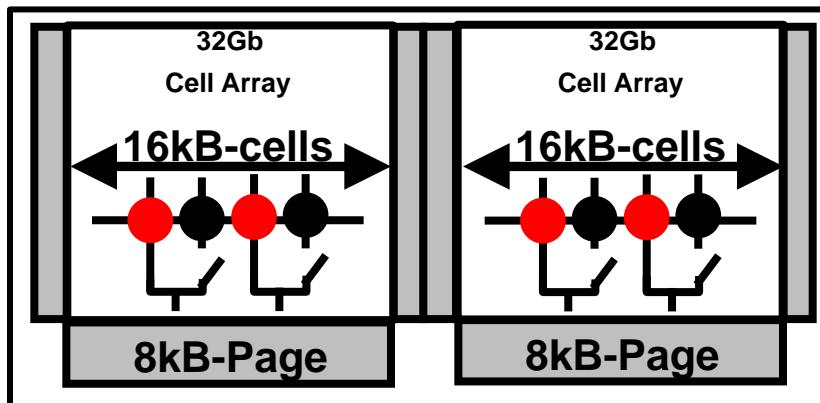
- Two different directions (**3bit/cell** and **2bit/cell**)
 - 3bit/cell enables highest Mb/mm²
 - 2bit/cell offers better performance and reliability

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- Introduction
- **Chip Architecture for Small Die Size**
 - Single-Array Configuration
 - One Sided All-Bit-Line(ABL) Architecture
 - High Speed Toggle Mode Interface
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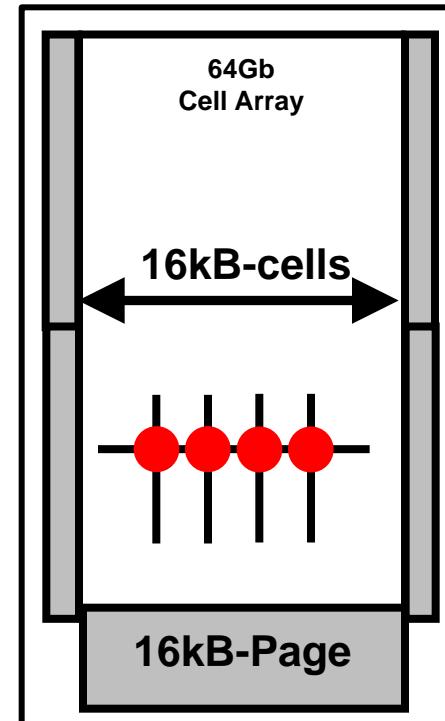
Single Array Configuration

Conventional Even / Odd Architecture



2-Plane array configuration

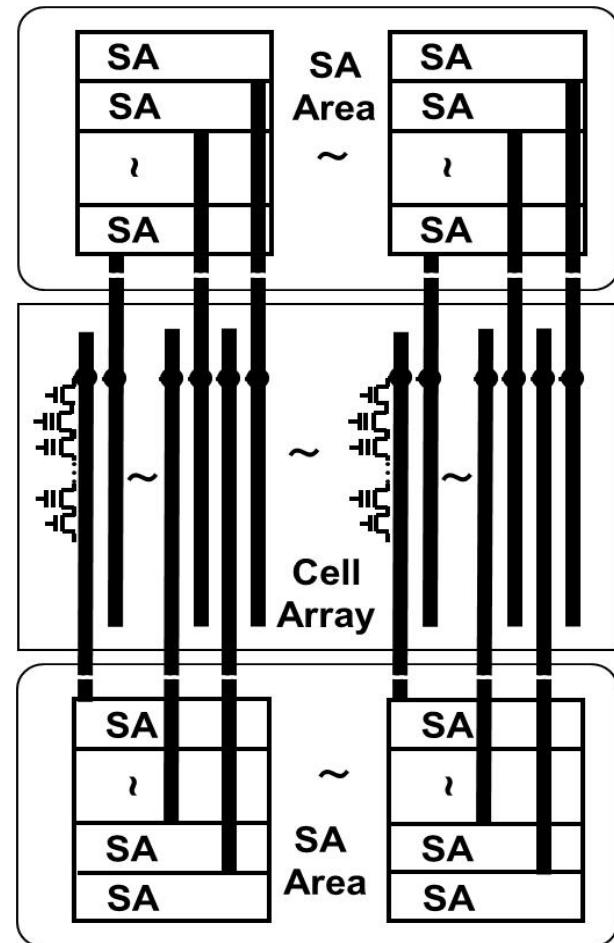
All-Bit-Line (ABL) Architecture



Single array configuration
⇒ Small Die size

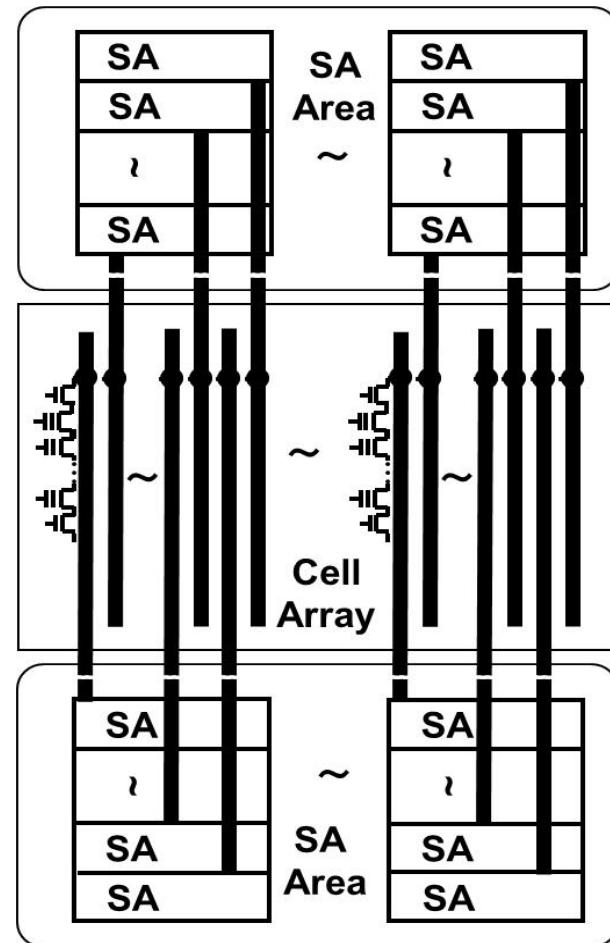
Two-Sided Sense Amp Architecture

- Half of SAs are placed on each side of the array due to complexity of SA layout.



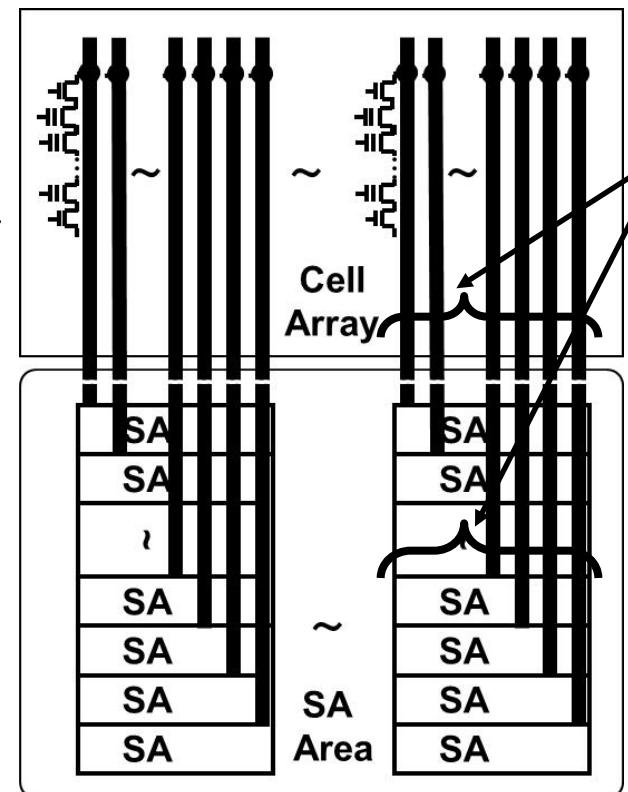
Conventional
Two-sided SA

One Sided ABL Architecture



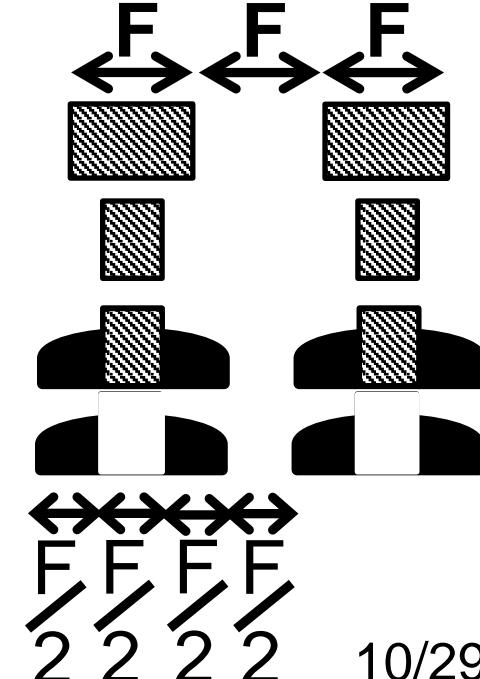
**Conventional
Two-sided SA**

- Same Metal pitch in SA as BL pitch
- Spacer patterning process



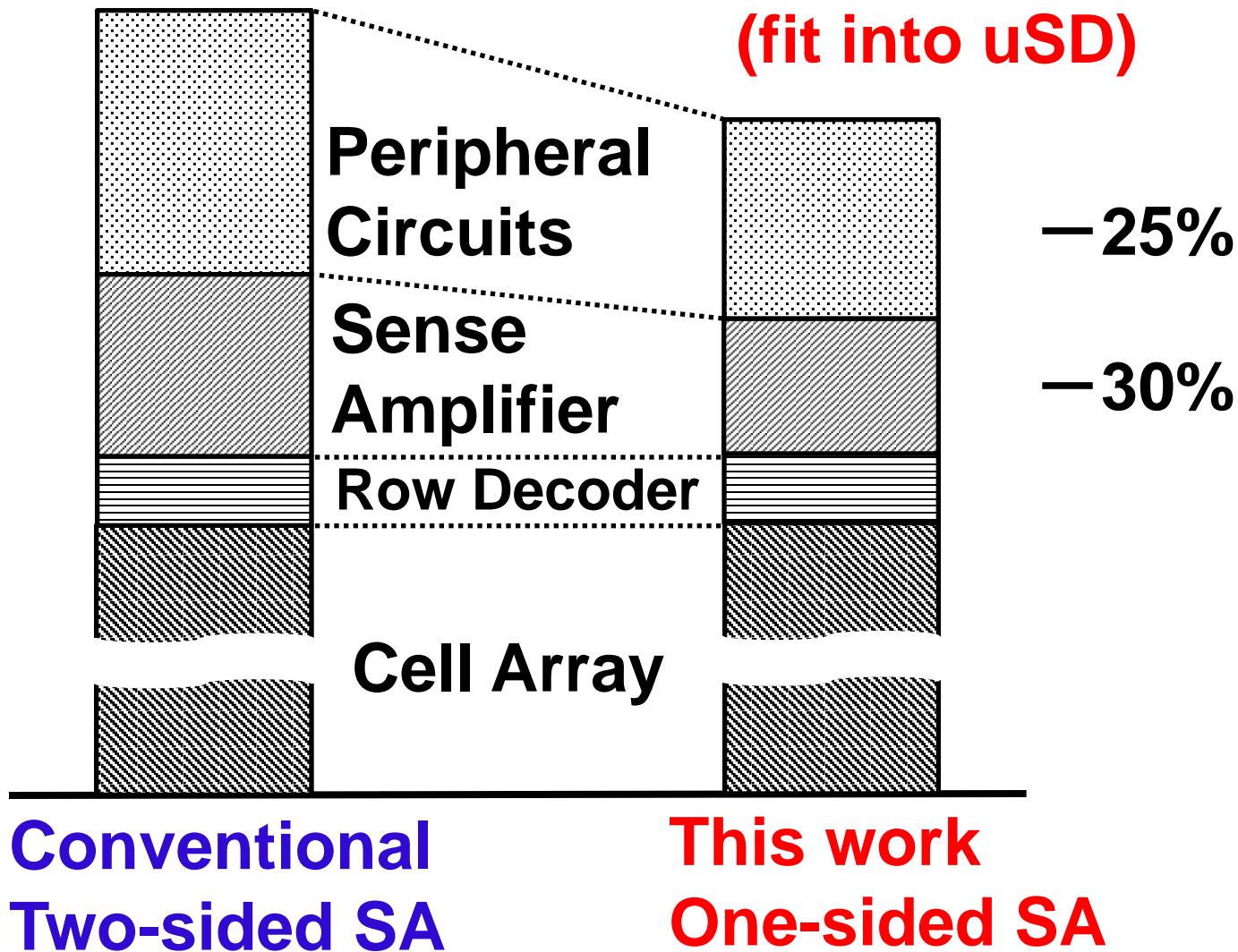
**This work
One-sided SA**

**Same Metal
pitch**



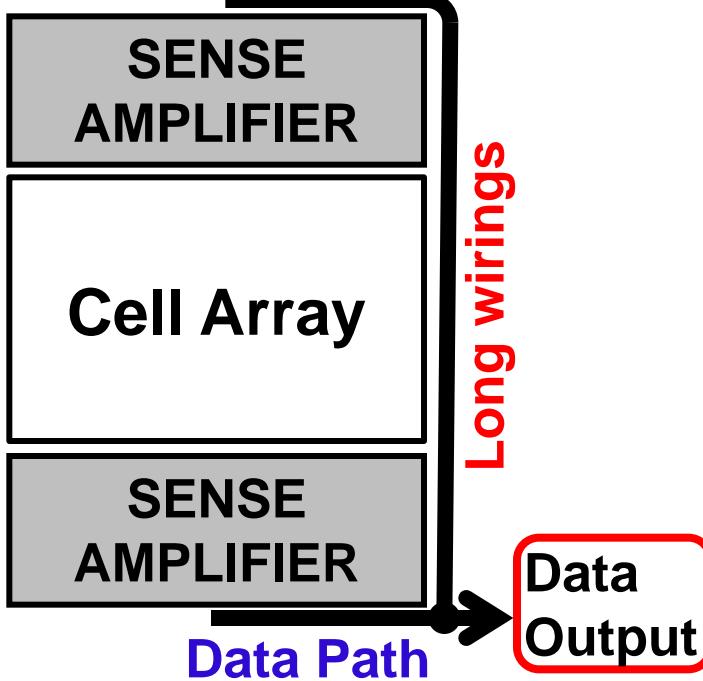
Die Size Reduction

117.3mm²(100%) → 112.8mm²(94%)

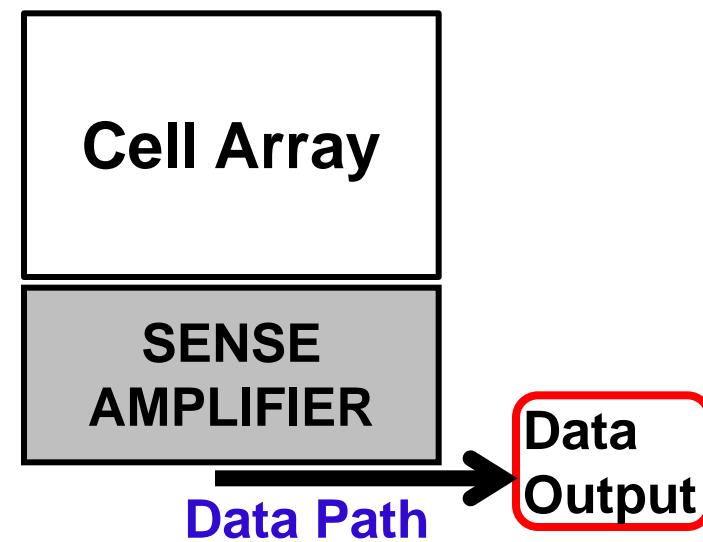


High Speed Toggle Mode Interface

Data Path



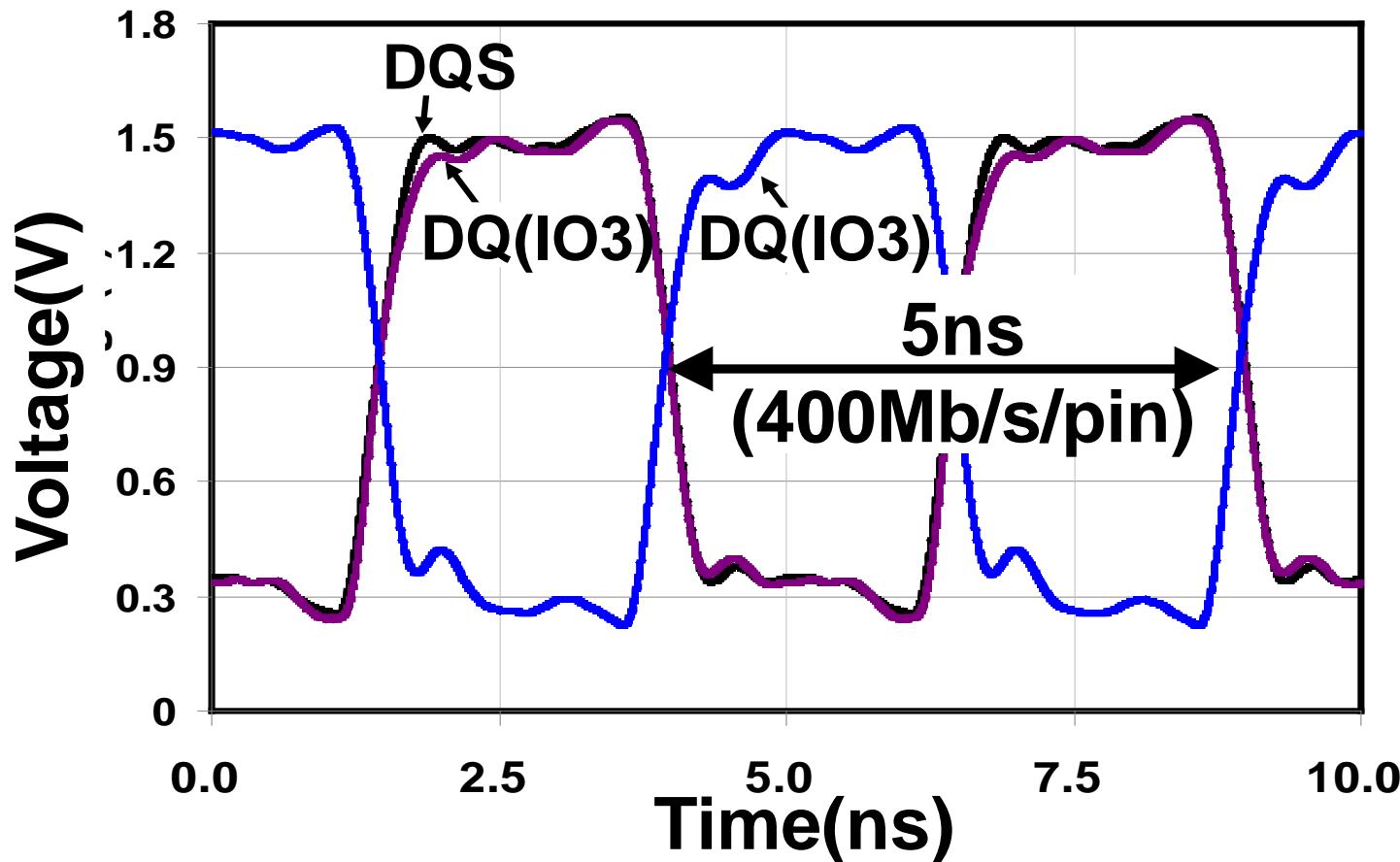
**Conventional
Two-sided sense amplifier**



**This work
One-sided sense amplifier**

- Minimized signal delays**
- Lower power consumption**

Measured Data Output Eye-Diagram



- 400Mb/s/pin@1.8V high-speed toggle mode interface is achieved!

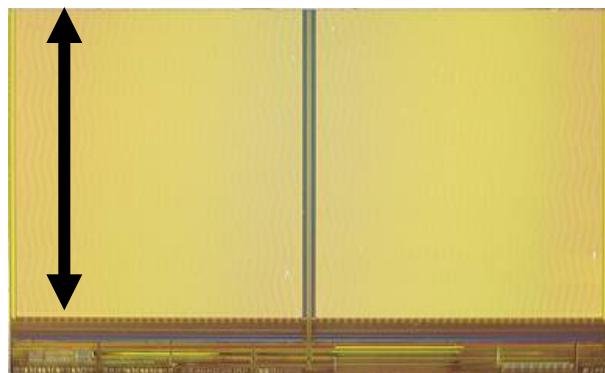
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- **MLC Program Techniques**
 - **Bit-Line Bias Acceleration (BLBA)**
 - **BC-States-First Program Algorithm**
- New Features(Read-Latency Reduction)
- Summary of Key Features
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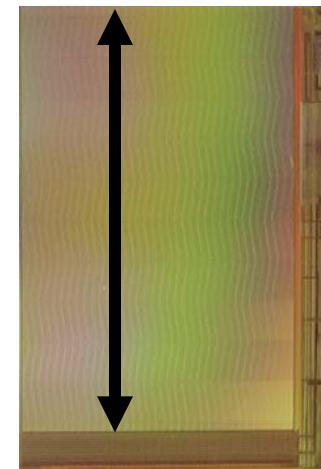
Bit-Line (BL) RC

24nm 64Gb D2



Bit-Line ~ 65,000cells

19nm 64Gb D2

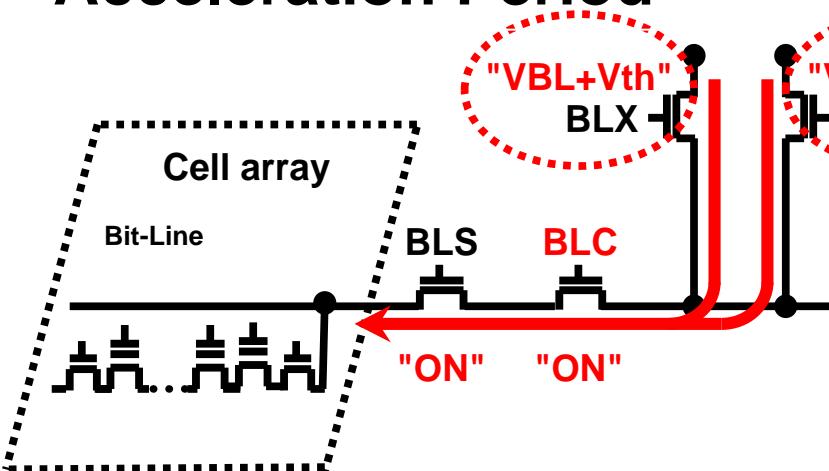


Bit-Line ~ 130,000cells

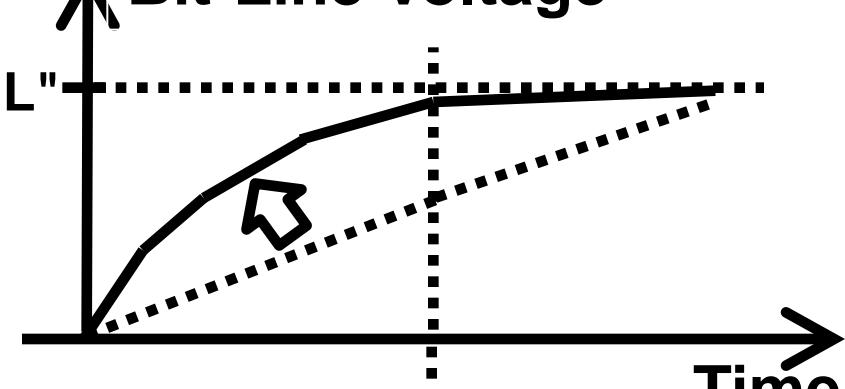
- Cells connecting to one Bit-Line is doubled
→ **Larger Bit-Line (BL) RC**

Bit-Line Bias Acceleration (BLBA)

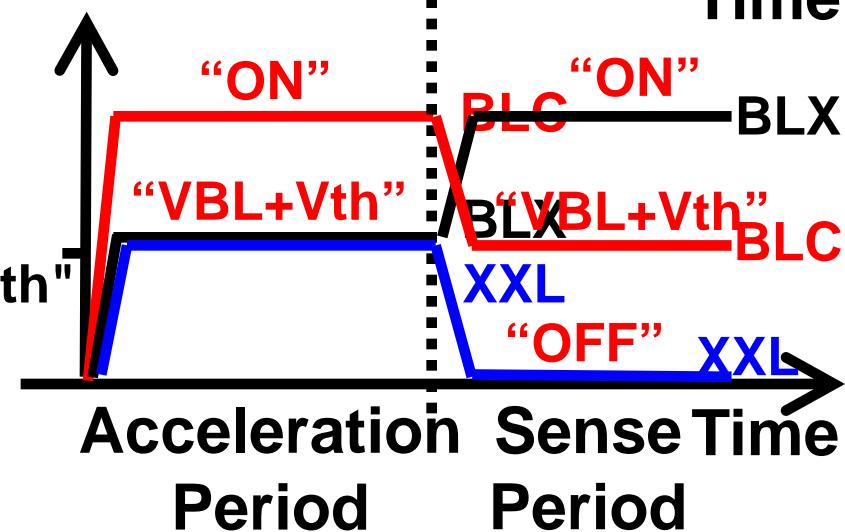
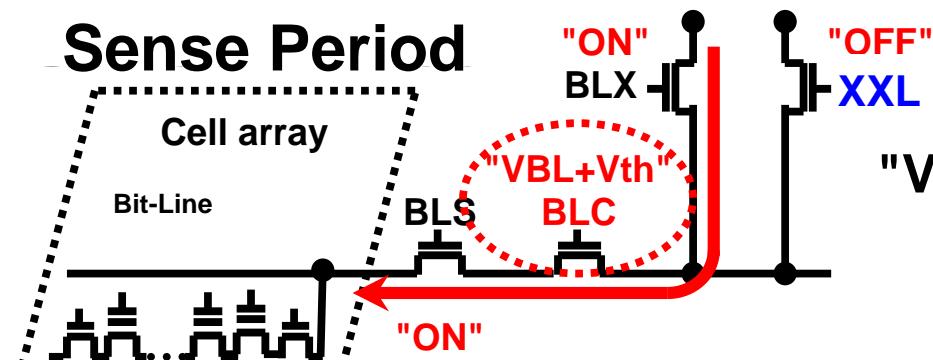
Acceleration Period



Bit-Line Voltage

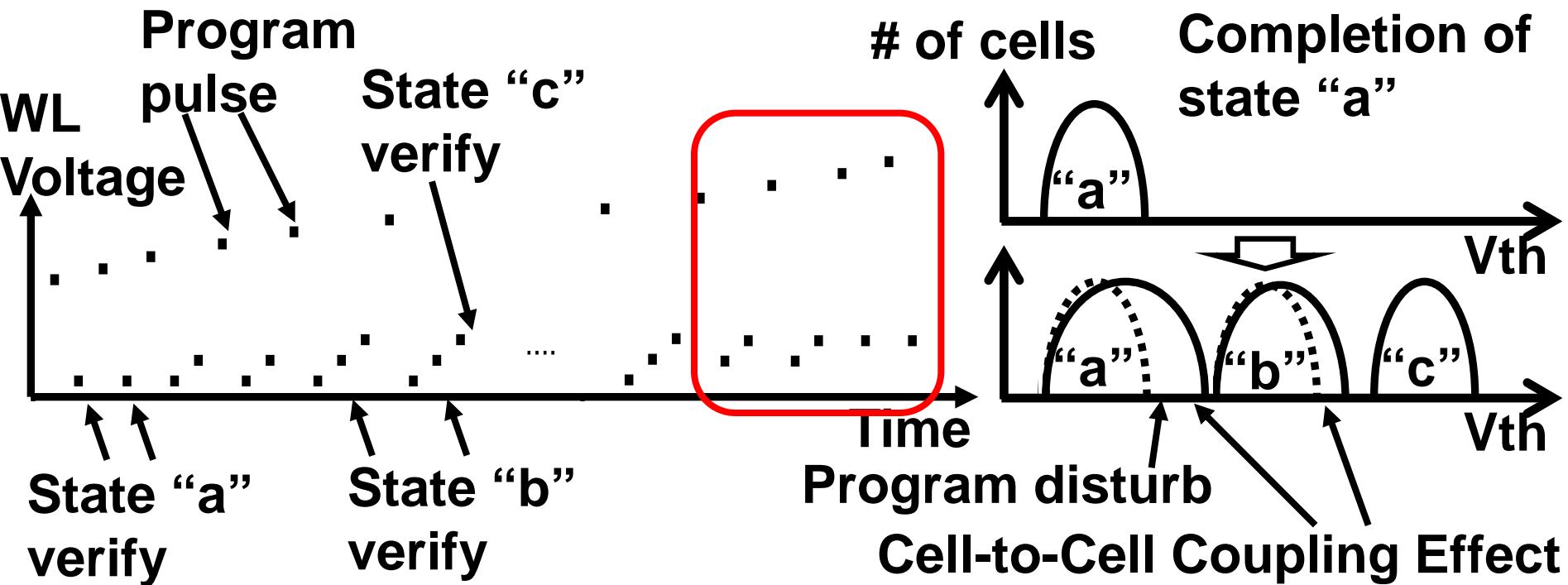


Sense Period



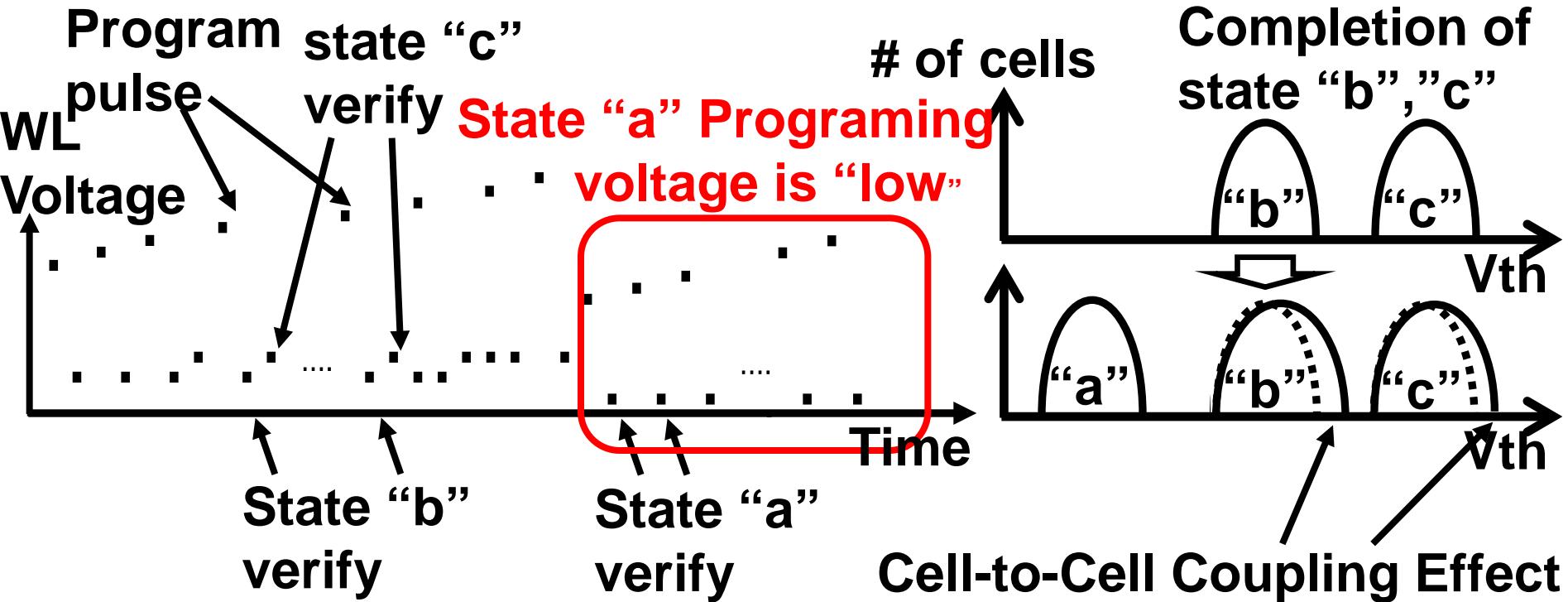
→ Bit-Line pre-charge time is reduced by 20%

Conventional-Program Algorithm



State "b" and "c" Programming voltage is "high"

BC-States-First Program Algorithm

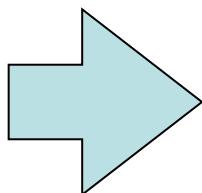


- “Program disturbs” and “cell-to-cell coupling effect” are suppressed
- Bigger incremental step size can be applied

MLC Program Improvement

- High program throughput with high reliability

	tProg reduction
◆ <u>All-Bit-Line</u> architecture (ABL)	----
◆ Bit-Line Bias Acceleration (BLBA)	(6%)
◆ BC-states-first program algorithm	(8%)
◆ Air Gap technology reduces FG coupling effect and word line(WL) RC	(10%)



**Program throughput : 15MB/s(16kB)
tProg : 1.1ms**

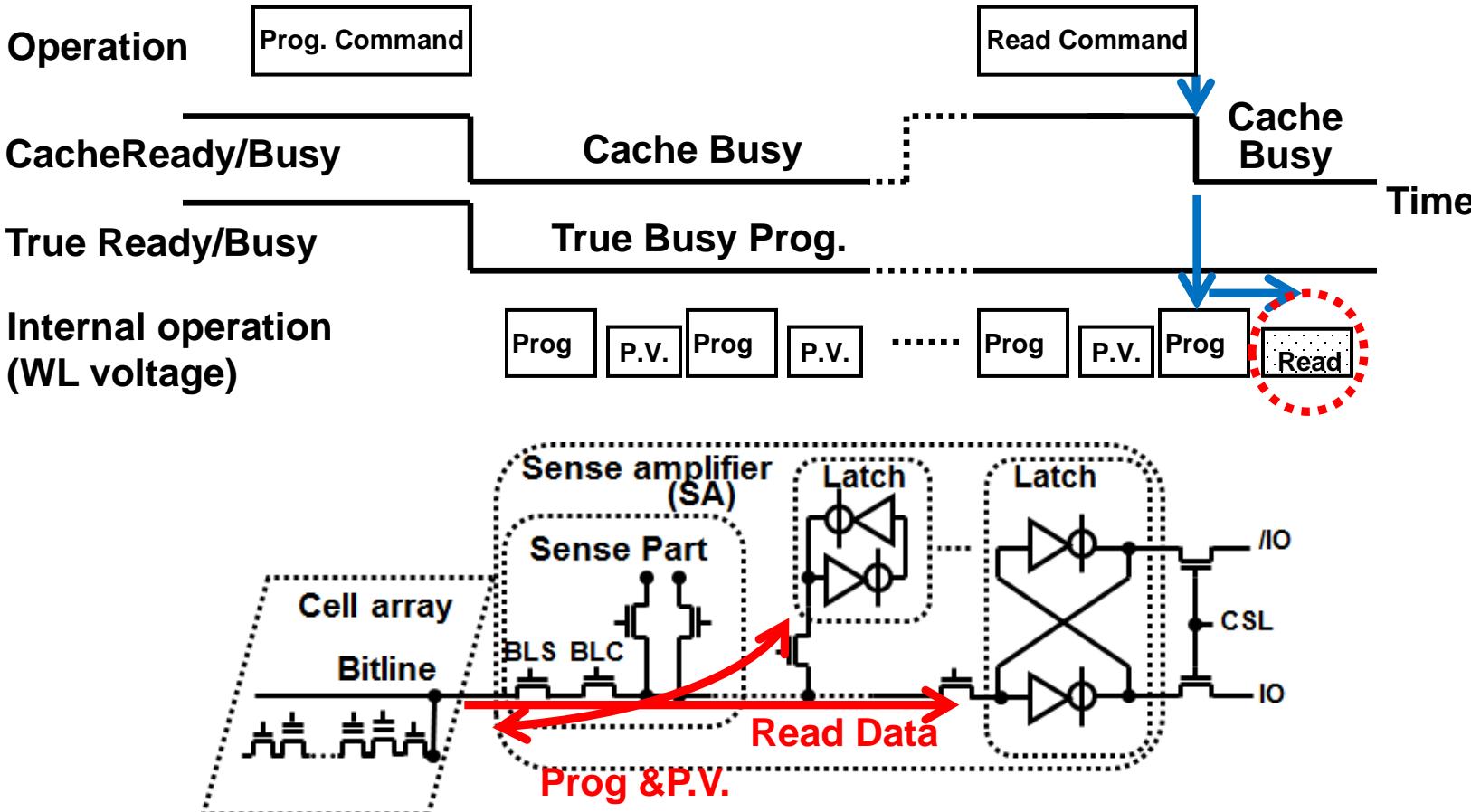


Outline



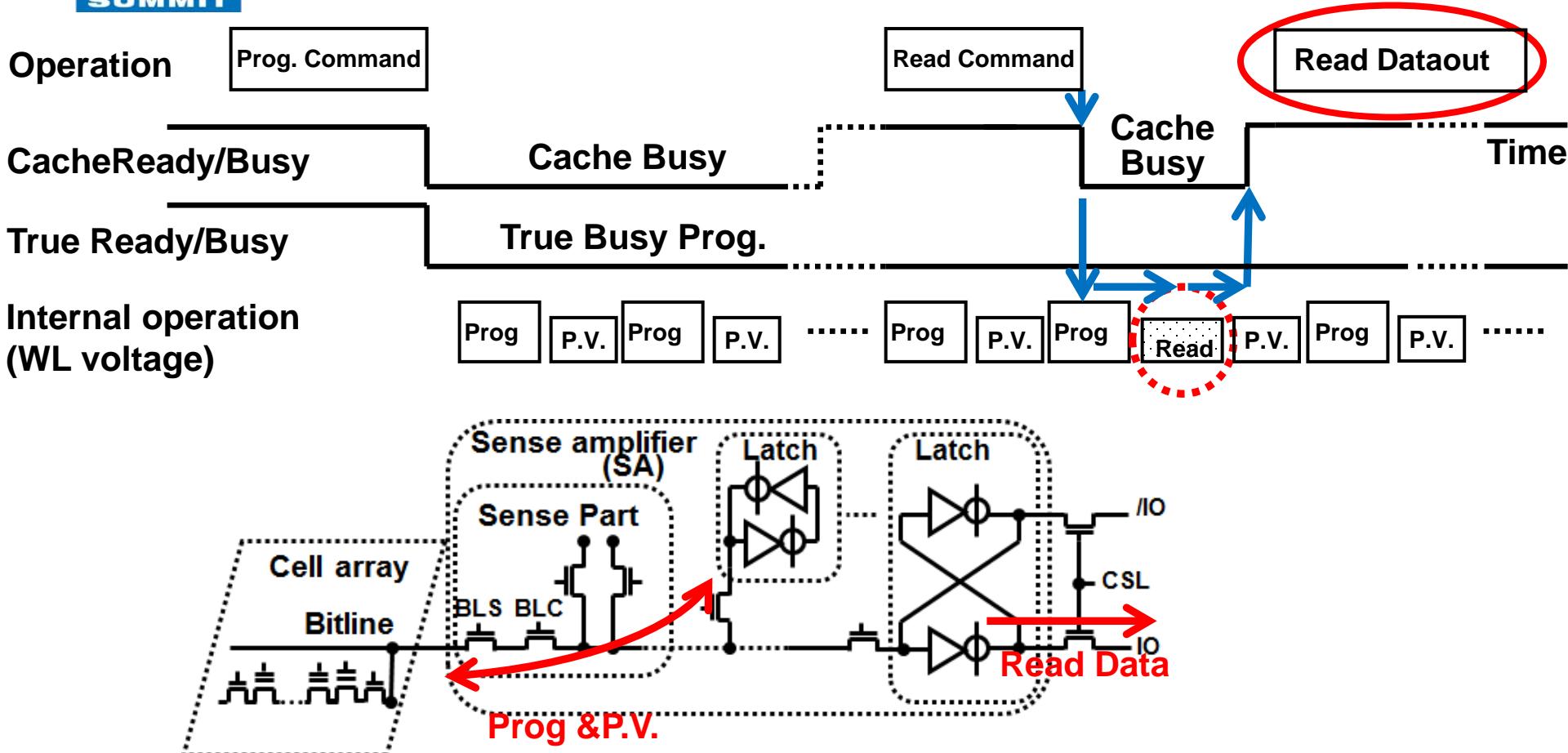
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Program-Suspend Function



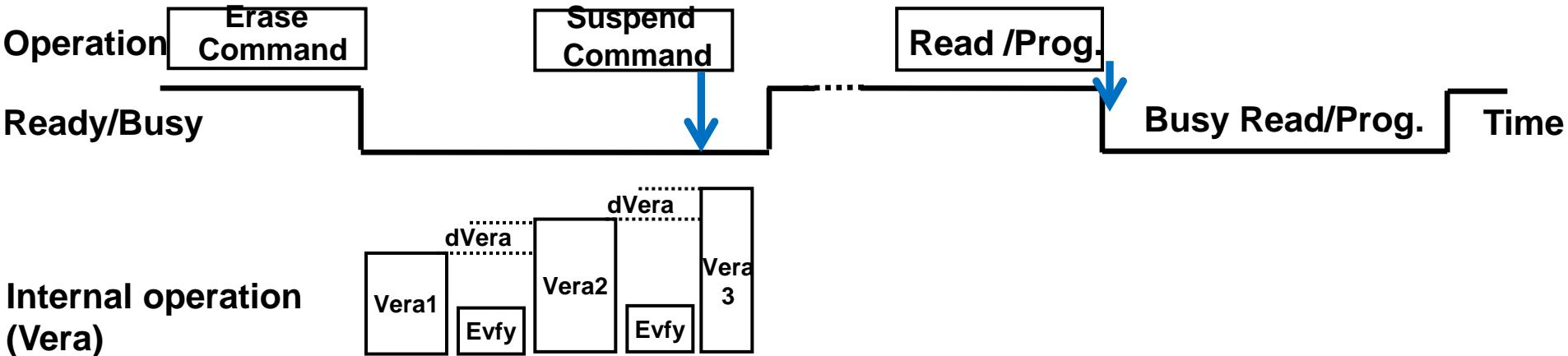
- Any page within any block can be read

Program-Suspend Function



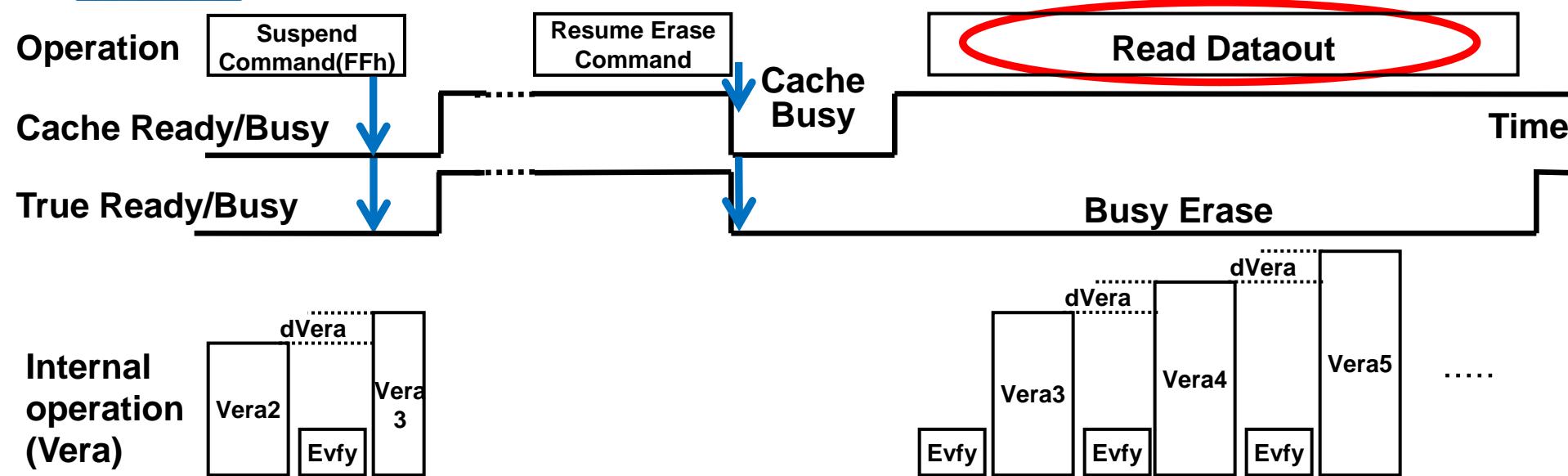
- Read data shifted out while program resumes

Erase-Suspend Function



- Same sequence as at Reset command.
- Program operation as well as read operation is available without any restrictions on address input

Erase-Suspend Function

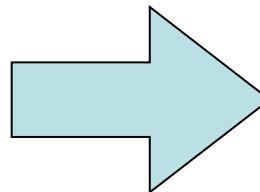


- Read data can be shifted out upon resume of erase sequence.

Read-Latency Reduction

- Read latency at program/erase is improved to 50us, which is comparable to normal read latency(~40us)

**1ms at program
4ms at erase**



50us

Conventional

- ◆ Program-suspend function
- ◆ Erase-suspend function

This work

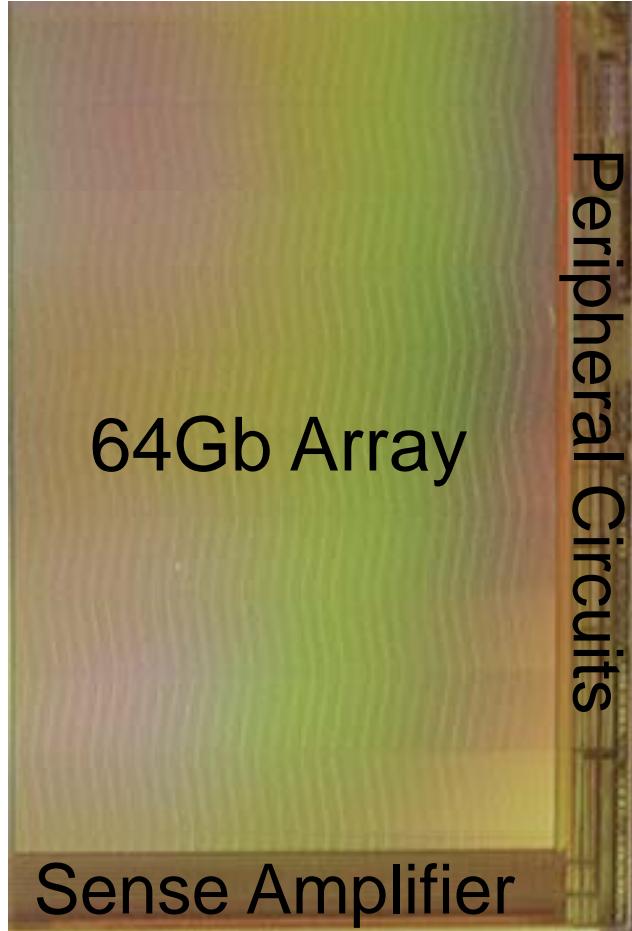


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Summary of Key Features



- Density: 64Gb, 2-bit/cell
- One sided ABL architecture
- Organization
 - ◆ 16kB / Page
 - ◆ 2 Pages / WL
 - ◆ Single-array configuration
- Program Throughput: 15MB/s
- Burst Cycle Time:
400Mb/s/pin Toggle mode @1.8V
- Power Supply: 2.7V to 3.6V
- Technology: 3-Metal 19nm CMOS
- DieSize: 112.8mm²

Conclusion

- ❑ For the first time, a 112.8mm² 64Gb Multi-level (2bits/cell) NAND flash memory is developed
 - ◆ 19nm CMOS technology
 - ◆ Single Array configuration
 - ◆ One sided All-Bit-Line
- ❑ 400Mb/s/pin 1.8V high speed Toggle Mode interface
- ❑ 15MB/s programing throughput with high reliability
 - ◆ Bit-Line Bias Acceleration(BLBA)
 - ◆ “BC” states-First program algorithm
- ❑ Read latency is improved by Program-Suspend and Erase-Suspend functions

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